

Title (en)
ELECTRON DENSITY MEASUREMENT AND CONTROL SYSTEM USING PLASMA-INDUCED CHANGES IN THE FREQUENCY OF A MICROWAVE OSCILLATOR

Title (de)
ELEKTRONENDICHTEMESSUNGS- UND REGELUNGSSYSTEM UNTER ANWENDUNG VON PLASMAINDUZIERTEN FREQUENZVERÄNDERUNGEN EINES MIKROWELLENOSZILLATORS

Title (fr)
SYSTEME DE MESURE ET DE CONTROLE DE DENSITE ELECTRONIQUE UTILISANT DES MODIFICATIONS EFFECTUEES PAR PLASMA DANS LA FREQUENCE D'UN OSCILLATEUR POUR HYPERFREQUENCES

Publication
EP 1218763 A4 20050202 (EN)

Application
EP 00947493 A 20000720

Priority
• US 0019535 W 20000720
• US 14487899 P 19990720

Abstract (en)
[origin: WO0106268A1] A method and system for measuring at least one of a plasma density and an electron density (e.g., in a range of 10^{10} to 10^{12} cm $^{-3}$). Measurement of at least one of the plasma density and the electron density enables plasma-assisted processes, such as depositions or etches, to be controlled using a feedback control. Both the measurement method and system generate a control voltage that in turn controls a plasma generator (205) to maintain at least one of the plasma density and the electron density at a pre-selected value.

IPC 1-7
G01R 27/04; **G01R 19/00**; **H01J 37/32**; **H05H 1/00**

IPC 8 full level
G01N 22/00 (2006.01); **G01R 19/00** (2006.01); **H01L 21/302** (2006.01); **H01L 21/3065** (2006.01); **H05H 1/00** (2006.01)

CPC (source: EP)
G01R 19/0061 (2013.01)

Citation (search report)
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• See references of WO 0106268A1

Designated contracting state (EPC)
AT BE CH CY DE DK ES FI FR GB GR IE IT LI LU MC NL PT SE

DOCDB simple family (publication)
WO 0106268 A1 20010125; **WO 0106268 A8 20010329**; CN 1162712 C 20040818; CN 1361867 A 20020731; EP 1218763 A1 20020703; EP 1218763 A4 20050202; JP 2003505668 A 20030212; JP 4339540 B2 20091007; KR 100712325 B1 20070502; KR 20020020787 A 20020315; TW 463531 B 20011111

DOCDB simple family (application)
US 0019535 W 20000720; CN 00810563 A 20000720; EP 00947493 A 20000720; JP 2001510852 A 20000720; KR 20027000688 A 20020117; TW 89114527 A 20000720